

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	21446	anthracene	US-PGPUB; USPAT	OR	ON	2006/08/14 15:39
L2	9629	anthracene and synthesis	US-PGPUB; USPAT	OR	ON	2006/08/14 15:39
L3	9287	anthracene and making	US-PGPUB; USPAT	OR	ON	2006/08/14 15:39
L4	11283	anthracene and make	US-PGPUB; USPAT	OR	ON	2006/08/14 15:39
L5	673162	anthracene and ammonium salt	US-PGPUB; USPAT	OR	ON	2006/08/14 15:40
L6	8525	anthracene and ammonium and salt	US-PGPUB; USPAT	OR	ON	2006/08/14 15:40
L7	4223	anthracene and ammonium and salt and making	US-PGPUB; USPAT	OR	ON	2006/08/14 15:40
L8	464	I7 and alkylating	US-PGPUB; USPAT	OR	ON	2006/08/14 15:40
L9	410	I7 and alkylating and ether	US-PGPUB; USPAT	OR	ON	2006/08/14 15:40
L10	76	I7 and alkylating and ether and phosphonium	US-PGPUB; USPAT	OR	ON	2006/08/14 15:41
L11	0	anthracenediol and I10	US-PGPUB; USPAT	OR	ON	2006/08/14 15:42
L12	36	anthracenediol	US-PGPUB; USPAT	OR	ON	2006/08/14 15:42
L13	0	I10 and I12	US-PGPUB; USPAT	OR	ON	2006/08/14 15:42
L14	671835	I12 and ammonium salt	US-PGPUB; USPAT	OR	ON	2006/08/14 15:42
L15	6	I12 and ammonium ADJ salt	US-PGPUB; USPAT	OR	ON	2006/08/14 15:43
S1	1	"6696112".pn.	US-PGPUB; USPAT	OR	ON	2006/08/14 12:06
S2	5	"539807".ap.	US-PGPUB; USPAT	OR	ON	2006/08/14 15:38

10/539,807 8-14-2006 Yung chu

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and display fields
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NEWS 14 JUL 14 FSTA enhanced with Japanese patents
NEWS 15 JUL 19 Coverage of Research Disclosure reinstated in DWPI
NEWS 16 AUG 09 INSPEC enhanced with 1898-1968 archive

NEWS EXPRESS JUNE 30 CURRENT WINDOWS VERSION IS V8.01b, CURRENT
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FILE 'HOME' ENTERED AT 08:28:40 ON 14 AUG 2006

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COST IN U.S. DOLLARS

FULL ESTIMATED COST

SINCE FILE

ENTRY

0.21

TOTAL

SESSION

0.21

FILE 'REGISTRY' ENTERED AT 08:28:54 ON 14 AUG 2006
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DICTIONARY FILE UPDATES: 11 AUG 2006 HIGHEST RN 900864-99-5

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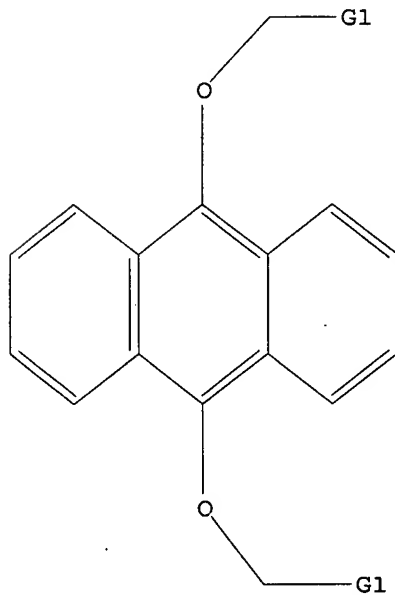
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L1 STRUCTURE UPLOADED

=> d
L1 HAS NO ANSWERS
L1 STR



G1 Ak,Cb

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=> s 11
SAMPLE SEARCH INITIATED 08:29:15 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED -- 739 TO ITERATE

100.0% PROCESSED 739 ITERATIONS 25 ANSWERS
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**
PROJECTED ITERATIONS: 13150 TO 16410
PROJECTED ANSWERS: 200 TO 800

L2 25 SEA SSS SAM L1

=> s l1 full
FULL SEARCH INITIATED 08:29:37 FILE 'REGISTRY'
FULL SCREEN SEARCH COMPLETED - 15657 TO ITERATE

100.0% PROCESSED 15657 ITERATIONS 454 ANSWERS
SEARCH TIME: 00.00.01

L3 454 SEA SSS FUL L1

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	167.38	167.59

FILE 'CAPLUS' ENTERED AT 08:30:07 ON 14 AUG 2006
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FILE LAST UPDATED: 13 Aug 2006 (20060813/ED)

Effective October 17, 2005, revised CAS Information Use Policies apply. They are available for your review at:

<http://www.cas.org/infopolicy.html>

=> s l3
L4 366 L3

=> s l4 and quaternary ammonium
127577 QUATERNARY
339 QUATERNARIES
127720 QUATERNARY
(QUATERNARY OR QUATERNARIES)
370638 AMMONIUM
402 AMMONIUMS
370782 AMMONIUM
(AMMONIUM OR AMMONIUMS)
63227 QUATERNARY AMMONIUM
(QUATERNARY (W) AMMONIUM)

L5

3 L4 AND QUATERNARY AMMONIUM

=> d ibib abs hitstr tot

L5 ANSWER 1 OF 3 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2003:271685 CAPLUS

DOCUMENT NUMBER: 138:287414

TITLE: Preparation of hydroquinone alkyl ethers

INVENTOR(S): Kubo, Hideo; Yamaguchi, Katsuji; Shirai, Akihiro

PATENT ASSIGNEE(S): Nippon Soda Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003104926	A2	20030409	JP 2001-299629	20010928
PRIORITY APPLN. INFO.:			JP 2001-299629	20010928

OTHER SOURCE(S): CASREACT 138:287414

AB Title compds., useful as sensitizers for photopolymn., etc. (no data), are prepd. by alkylation of hydroquinones by C.gtoeq.3 alkylating agents in the presence of bases and quaternary ammonium salts having C.gtoeq.5 substituents on N. Anthraquinone was alkylated by BuI in THF/H₂O in the presence of trioctylmethylammonium chloride, Na₂S₂O₄, and NaOH at 40-50.degree. for 5 h to give 85% 9,10-dibutoxyanthracene.

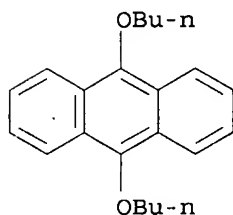
IT 76275-14-4P

RL: IMF (Industrial manufacture); SPN (Synthetic preparation); PREP (Preparation)

(prepn. of hydroquinone alkyl ethers from hydroquinones using quaternary ammonium salts)

RN 76275-14-4 CAPLUS

CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)



L5 ANSWER 2 OF 3 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2003:271684 CAPLUS

DOCUMENT NUMBER: 138:287413

TITLE: Preparation of anthracene diethers

INVENTOR(S): Nakano, Hironori; Honda, Hiroyuki; Numata, Shigeaki

PATENT ASSIGNEE(S): Kawasaki Kasei Chemicals, Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 7 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003104925	A2	20030409	JP 2001-299128	20010928

Current Application

CA 2510270	AA	20040708	CA 2002-2510270	20021219
WO 2004056734	A1	20040708	WO 2002-JP13314	20021219
WO 2004056734	C1	20050804		

W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW

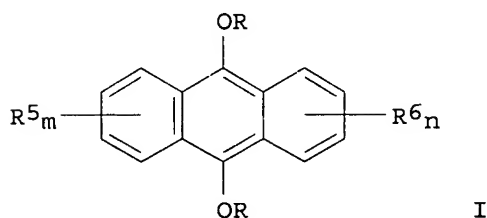
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AU 2002357616	A1	20040714	AU 2002-357616	20021219
EP 1574493	A1	20050914	EP 2002-808287	20021219

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US 2006079721	A1	20060413	US 2005-539807	20050620
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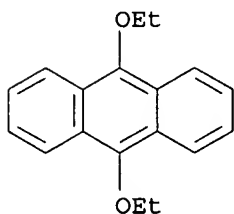
OTHER SOURCE(S): MARPAT 138:287413
GI



AB Anthracene diethers I. (R = alkyl, allyl, aryl, benzyl, hydroxyalkyl, alkoxyalkyl; R5, R6 = inert group; m, n = 0-4), useful as sensitizers for photocurable compns. (no data), are prepd. by reaction of 9,10-anthracenediols with etherifying agents in aq. media contg. alkalies and quaternary ammonium or phosphonium compds. 9,10-Anthracenediol Na salt was etherified with BuBr in H2O/MEK in the presence of Bu4NBr at 70.degree. for 4 h to give 90% 9,10-dibutoxyanthracene.

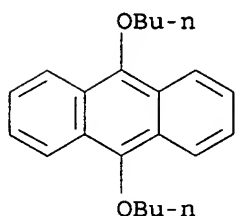
IT 68818-86-0P, 9,10-Diethoxyanthracene 76275-14-4P
479412-73-2P
RL: IMF (Industrial manufacture); SPN (Synthetic preparation); PREP (Preparation)
(prepn. of anthracene diethers from anthracenediols using quaternary ammonium or phosphonium compds.)

RN 68818-86-0 CAPLUS
CN Anthracene, 9,10-diethoxy- (6CI, 9CI) (CA INDEX NAME)



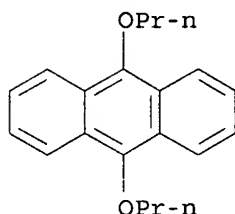
RN 76275-14-4 CAPLUS

CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)



RN 479412-73-2 CAPLUS

CN Anthracene, 9,10-dipropoxy- (9CI) (CA INDEX NAME)



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art*

Composition

L5 ANSWER 3 OF 3 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1987:59428 CAPLUS

DOCUMENT NUMBER: 106:59428

TITLE: Liquid crystal compositions

INVENTOR(S): Horimoto, Hikari; Mizutani, Yukio; Ogata, Takayuki

PATENT ASSIGNEE(S): Tokuyama Soda Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 13 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 61136584	A2	19860624	JP 1984-257349	19841207
JP 03080833	B4	19911226		

PRIORITY APPLN. INFO.: JP 1984-257349 19841207

AB The claimed liq. crystal-like comps. contain (1) a quaternary ammonium compd. having .gtoreq.2 linear hydrophobic groups or .gtoreq.1 hydrophobic group contg. stiff part within the chain and (2) a phosphoric group-contg. compd. having .gtoreq.2 linear hydrophobic groups. The liq. crystal-like comps. give membranes which show good water resistance and liq. crystal characteristics. The comps. are useful in prepg. synthetic biomembranes, display devices, and membranes for various sensors. Thus, a di(n-octadecyl)dimethylammonium bromide soln. and a di(n-dodecyl)monohydrogen phosphate soln. were mixed to give white ppt. which showed small soly. in water and showed liq. crystal phase at 56-115.

IT 106347-17-5

RL: PRP (Properties)

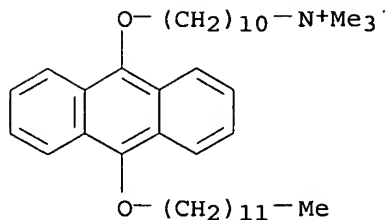
(prepns. of, as liq. crystal compds.)

RN 106347-17-5 CAPLUS

CN 1-Decanaminium, 10-[[10-(dodecyloxy)-9-anthracenyl]oxy]-N,N,N-trimethyl-, dioctadecyl phosphate (9CI) (CA INDEX NAME)

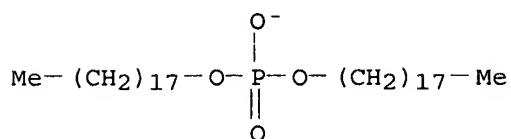
CM 1

CRN 106347-16-4
CMF C39 H62 N O2



CM 2

CRN 84841-00-9
CMF C36 H74 O4 P



=> s l4 and quaternary phosphonium
127577 QUATERNARY
339 QUATERNARIES
127720 QUATERNARY
(QUATERNARY OR QUATERNARIES)
15919 PHOSPHONIUM
80 PHOSPHONIUMS
15942 PHOSPHONIUM
(PHOSPHONIUM OR PHOSPHONIUMS)
1216 QUATERNARY PHOSPHONIUM
(QUATERNARY(W) PHOSPHONIUM)
L6 0 L4 AND QUATERNARY PHOSPHONIUM

=> s l4 and phase transfer
1690902 PHASE
353345 PHASES
1839674 PHASE
(PHASE OR PHASES)
781065 TRANSFER
25566 TRANSFERS
793479 TRANSFER
(TRANSFER OR TRANSFERS)
14182 PHASE TRANSFER
(PHASE(W) TRANSFER)
L7 1 L4 AND PHASE TRANSFER

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L7 ANSWER 1 OF 1 CAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2003:271685 CAPLUS
DOCUMENT NUMBER: 138:287414
TITLE: Preparation of hydroquinone alkyl ethers
INVENTOR(S): Kubo, Hideo; Yamaguchi, Katsuji; Shirai, Akihiro

PATENT ASSIGNEE(S): Nippon Soda Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

duplicate 1/3

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003104926	A2	20030409	JP 2001-299629	20010928
PRIORITY APPLN. INFO.:			JP 2001-299629	20010928

OTHER SOURCE(S): CASREACT 138:287414

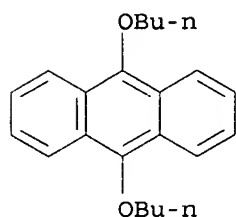
AB Title compds., useful as sensitizers for photopolymn., etc. (no data), are
 prepd. by alkylation of hydroquinones by C.gtoreq.3 alkylating agents in
 the presence of bases and quaternary ammonium salts having C.gtoreq.5
 substituents on N. Anthraquinone was alkylated by BuI in THF/H2O in the
 presence of trioctylmethylammonium chloride, Na2S2O4, and NaOH at
 40-50.degree. for 5 h to give 85% 9,10-dibutoxyanthracene.

IT 76275-14-4P

RL: IMF (Industrial manufacture); SPN (Synthetic preparation); PREP
 (Preparation)
 (prepn. of hydroquinone alkyl ethers from hydroquinones using
 quaternary ammonium salts)

RN 76275-14-4 CAPLUS

CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)



=> s 14 and quaternary salt
 127577 QUATERNARY
 339 QUATERNARIES
 127720 QUATERNARY
 (QUATERNARY OR QUATERNARIES)
 771808 SALT
 597517 SALTS
 1148926 SALT
 (SALT OR SALTS)
 6851 QUATERNARY SALT
 (QUATERNARY (W) SALT)
 L8 0 L4 AND QUATERNARY SALT

=> s 14 and etherifying agent
 1025 ETHERIFYING
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 (AGENT OR AGENTS)
 316 ETHERIFYING AGENT
 (ETHERIFYING (W) AGENT)
 L9 1 L4 AND ETHERIFYING AGENT

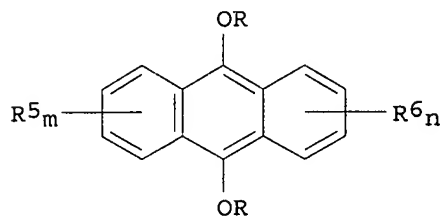
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L9 ANSWER 1 OF 1 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2003:271684 CAPLUS
DOCUMENT NUMBER: 138:287413
TITLE: Preparation of anthracene diethers
INVENTOR(S): Nakano, Hironori; Honda, Hiroyuki; Numata, Shigeaki
PATENT ASSIGNEE(S): Kawasaki Kasei Chemicals, Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 7 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

Current application

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003104925	A2	20030409	JP 2001-299128	20010928
CA 2510270	AA	20040708	CA 2002-2510270	20021219
WO 2004056734	A1	20040708	WO 2002-JP13314	20021219
WO 2004056734	C1	20050804		
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RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
AU 2002357616	A1	20040714	AU 2002-357616	20021219
EP 1574493	A1	20050914	EP 2002-808287	20021219
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, SK				
US 2006079721	A1	20060413	US 2005-539807	20050620
PRIORITY APPLN. INFO.:			JP 2001-299128	A 20010928
			WO 2002-JP13314	W 20021219
OTHER SOURCE(S):		MARPAT 138:287413		
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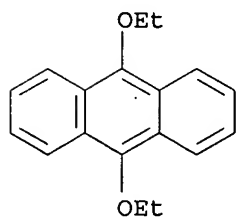
AB Anthracene diethers I (R = alkyl, allyl, aryl, benzyl, hydroxyalkyl, alkoxyalkyl; R5, R6 = inert group; m, n = 0-4), useful as sensitizers for photocurable compns. (no data), are prepd. by reaction of 9,10-anthracenediols with etherifying agents in aq. media contg. alkalies and quaternary ammonium or phosphonium compds. 9,10-Anthracenediol Na salt was etherified with BuBr in H2O/MEK in the presence of Bu4NBr at 70.degree. for 4 h to give 90% 9,10-dibutoxyanthracene.

IT 68818-86-0P, 9,10-Diethoxyanthracene 76275-14-4P
479412-73-2P
RL: IMF (Industrial manufacture); SPN (Synthetic preparation); PREP (Preparation)

(prepn. of anthracene diethers from anthracenediols using quaternary ammonium or phosphonium compds.)

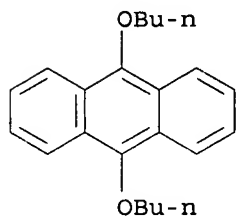
RN 68818-86-0 CAPLUS

CN Anthracene, 9,10-diethoxy- (6CI, 9CI) (CA INDEX NAME)



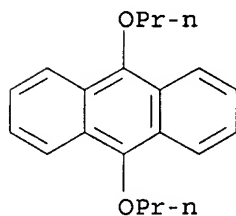
RN 76275-14-4 CAPLUS

CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)



RN 479412-73-2 CAPLUS

CN Anthracene, 9,10-dipropoxy- (9CI) (CA INDEX NAME)



=> s l4 and phosphonium

15919 PHOSPHONIUM

80 PHOSPHONIUMS

15942 PHOSPHONIUM

(PHOSPHONIUM OR PHOSPHONIUMS)

L10 3 L4 AND PHOSPHONIUM

=> d ibib abs hitstr tot

L10 ANSWER 1 OF 3 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2005:116518 CAPLUS

DOCUMENT NUMBER: 142:200135

TITLE: UV-curable coating compositions for food or soft drink cans or bottles and their coated products

INVENTOR(S): Nakajima, Yoshimoto

PATENT ASSIGNEE(S): Toyo Ink Mfg. Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 28 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2005036152	A2	20050210	JP 2003-276500	20030718
PRIORITY APPLN. INFO.:			JP 2003-276500	20030718

OTHER SOURCE(S): MARPAT 142:200135

AB Title compns. contain (A) photo cationic polymn. initiators selected from iodonium, sulfonium, sulfoxonium, and/or phosphonium salts, (B) 9,10-dialkoxyanthracenes (with C1-8 alkoxy groups substituted at 9 and 10 positions and C1-4 alkyl-substituted or unsubstituted 1-4 and 5-8 positions) as photo sensitizers, (C) room temp. solid epoxy compds. (contg. Me-substituted phenol, epichlorohydrin, and HCHO units), (D) alicyclic epoxy group-contg. cationic polymn. compds., and (E) pigments at A/(A + B + C + D + E) of 1.5-4.0% and C/(A + B + C + D + E) of 1-10%, and preferably E/(A + B + C + D + E) of .gtoreq.40% for TiO2 and .gtoreq.10% for Al pigment. A Sn-plated steel and PET laminate was coated with a white compn. contg. Cyacure UVI 6990 3, 9,10-dibutoxyanthracene 0.3, YDCN 704 5, Cyacure UVR 6110 41.70, and TiO2 50 parts and UV-cured at 40-70% relative humidity over 10-30 s to form a hard film with excellent adhesion.

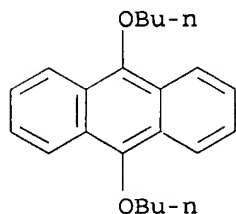
IT 76275-14-4

RL: CAT (Catalyst use); USES (Uses)

(photosensitizer; UV-curable alicyclic epoxy coatings contg. onium cationic initiators and anthracene photo sensitizers for food cans or bottles)

RN 76275-14-4 CAPLUS

CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)



L110 ANSWER 2 OF 3 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2003:271684 CAPLUS

DOCUMENT NUMBER: 138:287413

TITLE: Preparation of anthracene diethers

INVENTOR(S): Nakano, Hironori; Honda, Hiroyuki; Numata, Shigeaki

PATENT ASSIGNEE(S): Kawasaki Kasei Chemicals, Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 7 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

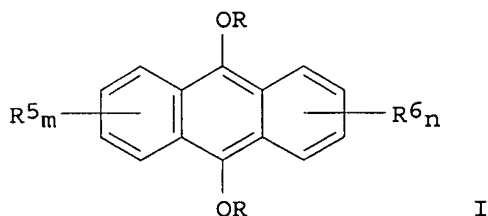
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003104925	A2	20030409	JP 2001-299128	20010928
CA 2510270	AA	20040708	CA 2002-2510270	20021219
WO 2004056734	A1	20040708	WO 2002-JP13314	20021219
WO 2004056734	C1	20050804		

W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,

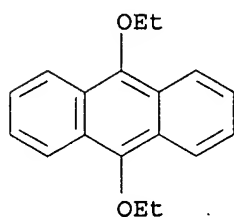
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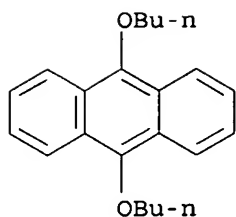
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 GM, HR, HU, ID, IL, IN, IS, KE, KG, KR, KZ, LC, LK, LR, LS, LT,
 LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT,
 RO, RU, SC, SD, SE, SG, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG,
 US, UZ, VC, VN, YU, ZA, ZM, ZW
 RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY,
 KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES,
 FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SI, SK, TR, BF, BJ, CF,
 CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG
 AU 2002357616 A1 20040714 AU 2002-357616 20021219
 EP 1574493 A1 20050914 EP 2002-808287 20021219
 R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
 IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, SK
 US 2006079721 A1 20060413 US 2005-539807 20050620
 PRIORITY APPLN. INFO.: JP 2001-299128 A 20010928
 WO 2002-JP13314 W 20021219
 OTHER SOURCE(S): MARPAT 138:287413
 GI



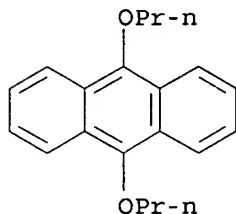
AB Anthracene diethers I (R = alkyl, allyl, aryl, benzyl, hydroxyalkyl, alkoxyalkyl; R5, R6 = inert group; m, n = 0-4), useful as sensitizers for photocurable compns. (no data), are prepd. by reaction of 9,10-anthracenediols with etherifying agents in aq. media contg. alkalies and quaternary ammonium or phosphonium compds.
 9,10-Anthracenediol Na salt was etherified with BuBr in H2O/MEK in the presence of Bu4NBr at 70.degree. for 4 h to give 90% 9,10-dibutoxyanthracene.
 IT 68818-86-0P, 9,10-Diethoxyanthracene 76275-14-4P
 479412-73-2P
 RL: IMF (Industrial manufacture); SPN (Synthetic preparation); PREP (Preparation)
 (prepn. of anthracene diethers from anthracenediols using quaternary ammonium or phosphonium compds.)
 RN 68818-86-0 CAPLUS
 CN Anthracene, 9,10-diethoxy- (6CI, 9CI) (CA INDEX NAME)



RN 76275-14-4 CAPLUS
 CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)



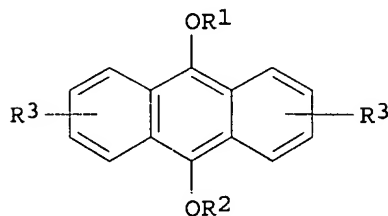
RN 479412-73-2 CAPLUS
CN Anthracene, 9,10-dipropoxy- (9CI) (CA INDEX NAME)



L10 ANSWER 3 OF 3 CAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2000:503506 CAPLUS
DOCUMENT NUMBER: 133:136808
TITLE: Radiation-curable compositions and manufacture of coatings therefrom
INVENTOR(S): Maruyama, Tsutomu
PATENT ASSIGNEE(S): Kansai Paint Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 14 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000204284	A2	20000725	JP 1999-8726	19990118
PRIORITY APPLN. INFO.:			JP 1999-8726	19990118
OTHER SOURCE(S):	MARPAT 133:136808			
GI				

Handwritten notes:
New composition
Not related
may



I

AB The compns. contain (A) photosensitizers I (R1, R2 = C1-8-alkyl; R3 = H, C1-4-alkyl) 0.01-5, (B) photo-cation initiators selected from iodonium salts, sulfonium salts, and phosphonium salts 0.1-20, and (C) cationically photopolymerizable compds. 100 parts. Thus, a compn. contg. 9,10-diethoxyanthracene 1, bis(4-tert-butylphenyl)iodonium hexafluorophosphate (BBI 102) 1, and 3,4-epoxycyclohexylmethyl

3,4-epoxycyclohexanecarboxylate (UVR 6110) 100 parts was applied on a substrate and radiation-cured to give a coating, showing spectral sensitivity 205-450 nm, gel fraction 87%, and pencil hardness 3-4 H.

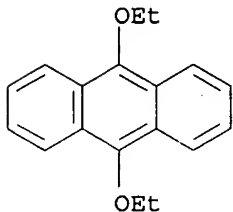
IT 68818-86-0, 9,10-Diethoxyanthracene 76275-14-4
205515-07-7, 2-Ethyl-9,10-diethoxyanthracene 205515-11-3
, 2-Methyl-9,10-diethoxyanthracene

RL: CAT (Catalyst use); USES (Uses)

(photosensitizer; radiation-curable coating compns. with good curability and hardness)

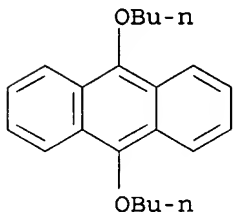
RN 68818-86-0 CAPLUS

CN Anthracene, 9,10-diethoxy- (6CI, 9CI) (CA INDEX NAME)



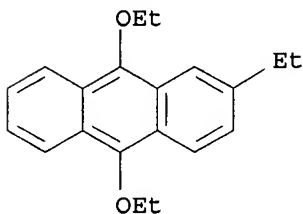
RN 76275-14-4 CAPLUS

CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)



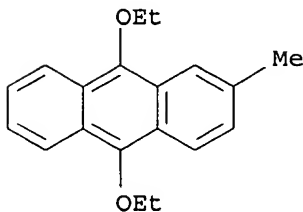
RN 205515-07-7 CAPLUS

CN Anthracene, 9,10-diethoxy-2-ethyl- (9CI) (CA INDEX NAME)



RN 205515-11-3 CAPLUS

CN Anthracene, 9,10-diethoxy-2-methyl- (9CI) (CA INDEX NAME)



=> s 14 and amonium salt

10 AMONIUM
771808 SALT
597517 SALTS
1148926 SALT
(SALT OR SALTS)
2 AMONIUM SALT
(AMONIUM(W)SALT)
L11 0 L4 AND AMONIUM SALT

=> s 14 and ammonium

370638 AMMONIUM
402 AMMONIUMS
370782 AMMONIUM
(AMMONIUM OR AMMONIUMS)
L12 9 L4 AND AMMONIUM

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L12 ANSWER 1 OF 9 CAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2005:1310229 CAPLUS
DOCUMENT NUMBER: 144:57628
TITLE: Photocurable dental composition
INVENTOR(S): Frances, Jean-Marc
PATENT ASSIGNEE(S): Fr.
SOURCE: U.S. Pat. Appl. Publ., 30 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2005277705	A1	20051215	US 2005-125133	20050510
FR 2872409	A1	20060106	FR 2004-7210	20040630
WO 2005120439	A1	20051222	WO 2005-FR1049	20050428

W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW

RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG

PRIORITY APPLN. INFO.:
FR 2004-5176 A 20040513
FR 2004-7210 A 20040630
US 2004-599021P P 20040806

OTHER SOURCE(S): MARPAT 144:57628

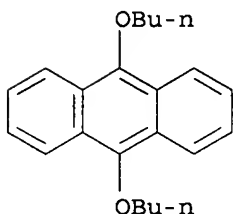
AB Dental compns. are described which are photocurable by radiation with a wavelength greater than 390 nm. The compns. include a cationically active compd., a dental filler, optionally a dispersant, a cationic photoinitiator and a photosensitizer which is a thioxanthone salt substituted by at least one group contg. an ammonium function. The compn. has the advantage of remedying the color stability problems of finished dental products after crosslinking. For example, dental composites comprising photosensitizer based on thioxanthenes contg. ammonium functionality, gave rise to an increased coloring

stability. An initial pink color change was obsd. with the comparative compn. comprising photosensitizer based on chloropropoxythioxanthone (CPTX), even at a low level of 60 ppm, which attenuates over time but which was still measurable after 5 days. In contrast, the use of thioxanthenes contg. ammonium functionality, did not give rise to this coloration defect at a low level and, surprisingly, made it possible to preserve a greater color stability.

IT 76275-14-4, 9,10-Dibutoxyanthracene
 RL: CAT (Catalyst use); USES (Uses)
 (PS-39; photocurable dental compn. comprising thioxanthone photosensitizer with increased color stability)

RN 76275-14-4 CAPLUS

CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)



L12 ANSWER 2 OF 9 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2004:118389 CAPLUS

DOCUMENT NUMBER: 140:147419

TITLE: Positive-working photosensitive heat-resistant resin precursor compositions for semiconductor devices

INVENTOR(S): Yumiba, Tomoyuki; Suwa, Atsushi; Tomikawa, Masao

PATENT ASSIGNEE(S): Toray Industries, Inc., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 23 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004045477	A2	20040212	JP 2002-199583	20020709
PRIORITY APPLN. INFO.:			JP 2002-199583	20020709

OTHER SOURCE(S): MARPAT 140:147419

AB The compns. with improved adhesion to substrates after heat-curing for interlayer insulator films and surface protection films of semiconductor devices, contain (A) polymers having main units
 [COR1(OH)p(CO2R3)nCONHR2(OH)q(CO2R4)oNH]m (R1, R2 = 2-8 valent C.gtoREQ.2 org. residue; R3, R4 = H, alkali metal ion, ammonium ion, C1-20 org. residue; m = 3-100,000; n, o = 0-2; p, q = 0-4; n + q > 0) and (B) compds. represented by R5R6C:N(CH2)a(SiR11R12O)bSiR13R14R15 or R7R8C:N(CH2)c(SiR16R17O)dSiR18R19(CH2)eN:CR9R10 (R5-R10 = C.gtoREQ.1 org. residue; R11-R19 = C1-6 hydrocarbonyl, C1-6 alkoxy; at least one of R11-R15 and one of R16-R19 = C1-6 alkoxy). Thus, a varnish contg. polyamic acid [prepd. from 4,4'-diaminodiphenyl ether, 1,3-bis(3-aminopropyl)tetramethyldisiloxane, pyromellitic anhydride, and 3,3',4,4'-benzophenonetetracarboxylic acid dianhydride] and 3-triethoxysilyl-N-(1,3-dimethylbutylidene)propylamine was applied on a Si wafer and heated to give a polyimide film showing high adhesion after pressure cooker test.

IT 119666-27-2

RL: CAT (Catalyst use); USES (Uses)

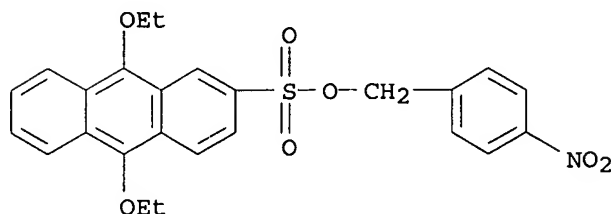
(photoacid generator; pos.-working photosensitive heat-resistant resin

late and not ODP

precursor compns. contg. aminoalkoxysilanes for semiconductor device insulator and protection films)

RN 119666-27-2 CAPLUS

CN 2-Anthracenesulfonic acid, 9,10-diethoxy-, (4-nitrophenyl)methyl ester (9CI) (CA INDEX NAME)



L12 ANSWER 3 OF 9 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2004:118071 CAPLUS

DOCUMENT NUMBER: 140:165070

TITLE: Heat-resistant resin precursor compositions and semiconductor devices therewith

INVENTOR(S): Yumiba, Tomoyuki; Minamihashi, Katsuya; Tomikawa, Masao

PATENT ASSIGNEE(S): Toray Industries, Inc., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 26 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

Late / Not OPP

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004043779	A2	20040212	JP 2003-119531	20030424
PRIORITY APPLN. INFO.:			JP 2002-126061	A 20020426

AB Title compns. comprise (A) polymers having repeating units [COR₁(OH)_p(COOR₃)_nCONHR₂(OH)_q(COOR₄)_oNH]_m as main components and (B) compds. (Z₁)_aR₅(Z₂)_b, wherein R₁, R₂ = divalent-octavalent org. groups contg. .gtoreq.2 carbon atoms; R₃, R₄ = H, alkali metal ion, ammonium ion, or C₁-20 org. group; R₅ = structure contg. .gtoreq.2 carbon atoms; m = 3-100,000 integer; n, o = 0-2 integer; p, q = 0-4 integer (p + q > 0); Z₁ = .gtoreq.1 structure selected from NR₆R₇, N:CR₈R₉, NR₁₀C(:O)R₁₁, or NHCOR₁₂OH; Z₂ = .gtoreq.1 structure selected from NR₆R₇, N:CR₈R₉, NR₁₀C(:O)R₁₁, NHCOR₁₂OH, vinyl, ethenyl, mercapto, or hydroxy group; R₆, R₇, R₈, R₉, R₁₀ = H or C₁-8 org. group; R₁₁, R₁₂ = C₁-8 org. group; and a, b = .gtoreq.1 integer. Thus, 4,4'-diaminodiphenyl ether 19, 1,3-bis(3-aminopropyl)tetramethyldisiloxane 1.2, pyromellitic anhydride 10.8, and 3,3',4,4'-benzophenonetetracarboxylic dianhydride 15 g were reacted at room temp. for 6 h to give a polyamic acid varnish, 3% 3-aminopropionitrile was added therein, applied on a copper-sputtered silicon wafer, a titanium-sputtered silicon wafer, and a gold-sputtered silicon wafer, and cured to give test pieces showing good adhesion between metal materials and a heat-resistant resin.

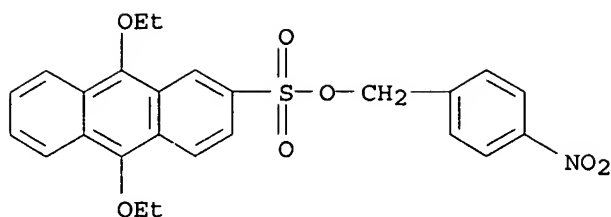
IT 119666-27-2

RL: CAT (Catalyst use); USES (Uses)

(photoacid generator; prepn. of heat-resistant resin precursor compns. for semiconductor devices)

RN 119666-27-2 CAPLUS

CN 2-Anthracenesulfonic acid, 9,10-diethoxy-, (4-nitrophenyl)methyl ester (9CI) (CA INDEX NAME)



L12 ANSWER 4 OF 9 CAPLUS COPYRIGHT 2006 ACS on STN
 ACCESSION NUMBER: 2003:271685 CAPLUS
 DOCUMENT NUMBER: 138:287414
 TITLE: Preparation of hydroquinone alkyl ethers
 INVENTOR(S): Kubo, Hideo; Yamaguchi, Katsuji; Shirai, Akihiro
 PATENT ASSIGNEE(S): Nippon Soda Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

duplicate

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003104926	A2	20030409	JP 2001-299629	20010928
PRIORITY APPLN. INFO.:			JP 2001-299629	20010928

OTHER SOURCE(S): CASREACT 138:287414

AB Title compds., useful as sensitizers for photopolymn., etc. (no data), are prepd. by alkylation of hydroquinones by C.gtoreq.3 alkylating agents in the presence of bases and quaternary ammonium salts having C.gtoreq.5 substituents on N. Anthraquinone was alkylated by BuI in THF/H2O in the presence of trioctylmethylammonium chloride, Na2S2O4, and NaOH at 40-50.degree. for 5 h to give 85% 9,10-dibutoxyanthracene.

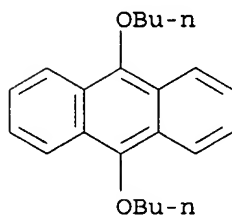
IT 76275-14-4P

RL: IMF (Industrial manufacture); SPN (Synthetic preparation); PREP (Preparation)

(prepn. of hydroquinone alkyl ethers from hydroquinones using quaternary ammonium salts)

RN 76275-14-4 CAPLUS

CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)

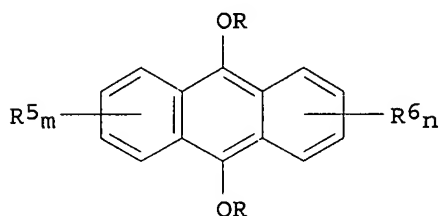


Current app/duplicate

L12 ANSWER 5 OF 9 CAPLUS COPYRIGHT 2006 ACS on STN
 ACCESSION NUMBER: 2003:271684 CAPLUS
 DOCUMENT NUMBER: 138:287413
 TITLE: Preparation of anthracene diethers
 INVENTOR(S): Nakano, Hironori; Honda, Hiroyuki; Numata, Shigeaki
 PATENT ASSIGNEE(S): Kawasaki Kasei Chemicals, Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 7 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent

LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003104925	A2	20030409	JP 2001-299128	20010928
CA 2510270	AA	20040708	CA 2002-2510270	20021219
WO 2004056734	A1	20040708	WO 2002-JP13314	20021219
WO 2004056734	C1	20050804		
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
AU 2002357616	A1	20040714	AU 2002-357616	20021219
EP 1574493	A1	20050914	EP 2002-808287	20021219
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, SK				
US 2006079721	A1	20060413	US 2005-539807	20050620
PRIORITY APPLN. INFO.:			JP 2001-299128	A 20010928
			WO 2002-JP13314	W 20021219
OTHER SOURCE(S):		MARPAT 138:287413		
GI				

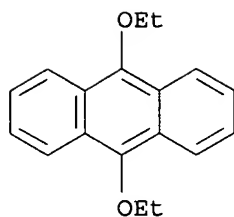


AB Anthracene diethers I (R = alkyl, allyl, aryl, benzyl, hydroxyalkyl, alkoxyalkyl; R5, R6 = inert group; m, n = 0-4), useful as sensitizers for photocurable compns. (no data), are prepd. by reaction of 9,10-anthracenediols with etherifying agents in aq. media contg. alkalies and quaternary ammonium or phosphonium compds. 9,10-Anthracenediol Na salt was etherified with BuBr in H2O/MEK in the presence of Bu4NBr at 70.degree. for 4 h to give 90% 9,10-dibutoxyanthracene.

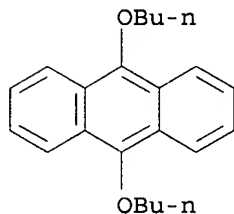
IT 68818-86-0P, 9,10-Diethoxyanthracene 76275-14-4P
 479412-73-2P
 RL: IMF (Industrial manufacture); SPN (Synthetic preparation); PREP (Preparation)
 (prepn. of anthracene diethers from anthracenediols using quaternary ammonium or phosphonium compds.)

RN 68818-86-0 CAPLUS

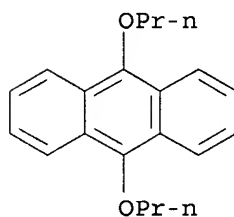
CN Anthracene, 9,10-diethoxy- (6CI, 9CI) (CA INDEX NAME)



RN 76275-14-4 CAPLUS
CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)



RN 479412-73-2 CAPLUS
CN Anthracene, 9,10-dipropoxy- (9CI) (CA INDEX NAME)



L12 ANSWER 6 OF 9 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2002:36602 CAPLUS

DOCUMENT NUMBER: 136:103469

TITLE: Heat-resistant resin compositions useful for semiconductor devices with good adhesion and low absorbance

INVENTOR(S): Okuda, Ryoji; Fujiwara, Takenori; Tomikawa, Masao

PATENT ASSIGNEE(S): Toray Industries, Inc., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 17 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002012761	A2	20020115	JP 2001-112287	20010411
PRIORITY APPLN. INFO.:			JP 2000-129395	A 20000428

AB The comps. useful for surface protective and insulative uses for semiconductor devices contain triazine and/or vinyl group-contg. compds. and [COR1(OH)p(CO2R3)nCONHR2(OH)q(CO2R4)ONH]m [R1, R2 = (2-8 valent) org. group contg. ≥ 2 C atoms; R3, R4 = H, alkali metal ion, ammonium ion, C1-20 org. group; m = 3-100,000; n = 0-2; p, q = 0-4; n + q > 0]. Thus, cyanuric acid triallyl ester was mixed with a mixt.

Composition/ not process for making

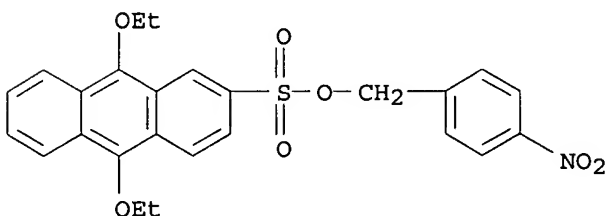
contg. 4,4'-diaminodiphenyl ether-pyromellitic anhydride-3,3',4,4'-benzophenonetetracarboxylic dianhydride copolymer, N,N-dimethylaminoethylmethacrylamide, N-phenylglycin, ethylene glycol dimethacrylate, and 3,3'-carbonylbis(7-diethylaminocoumalin), the resulting mixt. was applied on a glass substrate, dried, and cured to give a 1 .mu.m film showing absorbance 0.035 at 500 nm.

IT 119666-27-2

RL: MOA (Modifier or additive use); USES (Uses)
(photoacid generator; heat-resistant resin compns. useful for semiconductor devices with good adhesion and low absorbance)

RN 119666-27-2 CAPLUS

CN 2-Anthracenesulfonic acid, 9,10-diethoxy-, (4-nitrophenyl)methyl ester
(9CI) (CA INDEX NAME)



L12 ANSWER 7 OF 9 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2002:10872 CAPLUS

DOCUMENT NUMBER: 136:93561

TITLE: Optical imaging device with flat display panels equipped with electrodes partially coated with dielectric material of positive-working light-sensitive polyimide

INVENTOR(S): Okuda, Ryoji; Fujimori, Shigeo; Oka, Tetsuo; Tomikawa, Masao

PATENT ASSIGNEE(S): Toray Industries, Inc., Japan

SOURCE: PCT Int. Appl., 52 pp.

CODEN: PIXXD2

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2002001922	A1	20020103	WO 2001-JP5466	20010626
W: KR, US				
RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR				
JP 2002091343	A2	20020327	JP 2001-189396	20010622
JP 2002116715	A2	20020419	JP 2001-189397	20010622
TW 525407	B	20030321	TW 2001-90115392	20010626
EP 1296540	A1	20030326	EP 2001-941258	20010626
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, FI, CY, TR				
US 2002162998	A1	20021107	US 2002-69769	20020228
US 6696112	B2	20040224		

PRIORITY APPLN. INFO.: JP 2000-194019 A 20000628
WO 2001-JP5466 W 20010626

AB A display comprises a first electrode having an insulating layer in a manner such that a part of the first electrode is exposed, and a second electrode disposed so as to be opposed to the first electrode having the insulating layer, wherein the the insulating layer comprises a pos. photosensitive polyimide with structural unit [-CO-R1(OH)p(COOR3)n-CO-NH-

display, not process

Not

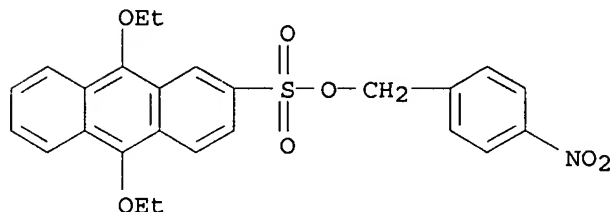
R2(OH)q(COOR4)o-NH-]m (R1-2 = C,gtoreq.2 2-8 valent orgs.; R3-4 = H, alkali metal ion, ammonium ion, Cl-20 orgs.; m = 3-100,000; n, o = 0-2 integer; p, q = 0-4 integer, p+q>0) and an agent generating an acid by a light. The optical imaging device has easily patterned polyimide insulating layer on the electrodes.

IT 119666-27-2

RL: RCT (Reactant); RACT (Reactant or reagent)
(photoresist compn. for dielec. coating on electrodes of optical imaging devices)

RN 119666-27-2 CAPLUS

CN 2-Anthracenesulfonic acid, 9,10-diethoxy-, (4-nitrophenyl)methyl ester
(9CI) (CA INDEX NAME)



Not process for making

REFERENCE COUNT: 9 THERE ARE 9 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L12 ANSWER 8 OF 9 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1990:581220 CAPLUS

DOCUMENT NUMBER: 113:181220

TITLE: An aqueous base developable novel deep-UV resist for krypton fluoride (KrF) excimer laser lithography

AUTHOR(S): Murata, Makoto; Takahashi, Toshihiko; Koshiba, Mitsunobu; Kawamura, Shinichi; Yamaoka, Tsuguo
CORPORATE SOURCE: Electron. Res. Lab., Japan Synth. Rubber Co., Ltd., Kawasaki, 215, Japan

SOURCE: Proceedings of SPIE-The International Society for Optical Engineering (1990), 1262(Adv. Resist Technol. Process. 7), 8-15

CODEN: PSISDG; ISSN: 0277-786X

DOCUMENT TYPE: Journal

LANGUAGE: English

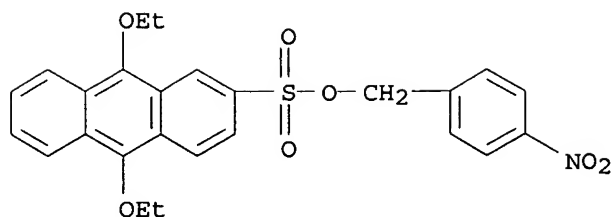
AB A novel deep-UV resist of poly(p-trimethylsilyloxystyrene) and p-nitrobenzyl 9-10-diethoxyanthracene-2-sulfonate is capable of resolving 0.3 .mu. lines and spaces with steep sidewalls at 0.8 .mu. thickness by a KrF excimer laser stepper. Wet development in a conventional tetramethylammonium hydroxide developer caused no crit. thickness loss in the unexposed area. Owing to its O plasma durability, this resist works as a top layer of a bilayer resist.

IT 119666-27-2

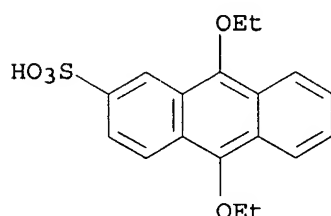
RL: USES (Uses)
(excimer laser submicron lithog. deep-UV photoresist contg., aq. base developable)

RN 119666-27-2 CAPLUS

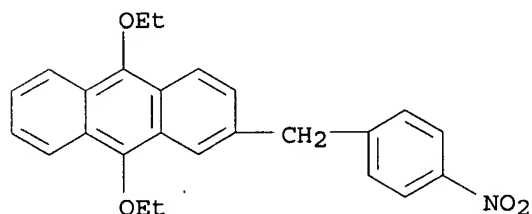
CN 2-Anthracenesulfonic acid, 9,10-diethoxy-, (4-nitrophenyl)methyl ester
(9CI) (CA INDEX NAME)



IT 123131-61-3P, 9,10-Diethoxyanthracene-2-sulfonic acid
 RL: RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
 (formation and reaction of, in deep-UV exposed submicron lithog.
 photoresist)
 RN 123131-61-3 CAPLUS
 CN 2-Anthracenesulfonic acid, 9,10-diethoxy- (9CI) (CA INDEX NAME)



IT 129995-19-3, 9,10-Diethoxy-2-p-nitrobenzylanthracene
 RL: USES (Uses)
 (in deep-UV exposed submicron lithog. photoresist)
 RN 129995-19-3 CAPLUS
 CN Anthracene, 9,10-diethoxy-2-[(4-nitrophenyl)methyl]- (9CI) (CA INDEX NAME)



*Liquid composition,
 but process for making*

L12 ANSWER 9 OF 9 CAPLUS COPYRIGHT 2006 ACS on STN
 ACCESSION NUMBER: 1987:59428 CAPLUS
 DOCUMENT NUMBER: 106:59428
 TITLE: Liquid crystal compositions
 INVENTOR(S): Horimoto, Hikari; Mizutani, Yukio; Ogata, Takayuki
 PATENT ASSIGNEE(S): Tokuyama Soda Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 13 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 61136584	A2	19860624	JP 1984-257349	19841207
JP 03080833	B4	19911226		

PRIORITY APPLN. INFO.:

JP 1984-257349

19841207

AB The claimed liq. crystal-like compns. contain (1) a quaternary ammonium compd. having .gtoreq.2 linear hydrophobic groups or .gtoreq.1 hydrophobic group contg. stiff part within the chain and (2) a phosphoric group-contg. compd. having .gtoreq.2 linear hydrophobic groups. The liq. crystal-like compns. give membranes which show good water resistance and liq. crystal characteristics. The compns. are useful in prepg. synthetic biomembranes, display devices, and membranes for various sensors. Thus, a di(n-octadecyl)dimethylammonium bromide soln. and a di(n-dodecyl)monohydrogen phosphate soln. were mixed to give white ppt. which showed small soly. in water and showed liq. crystal phase at 56-115.

IT 106347-17-5

RL: PRP (Properties)

(prepns. of, as liq. crystal compds.)

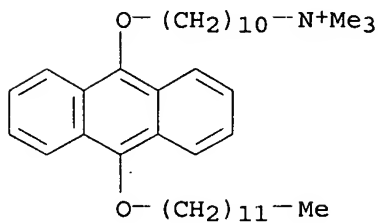
RN 106347-17-5 CAPLUS

CN 1-Decanaminium, 10-[[10-(dodecyloxy)-9-anthracenyl]oxy]-N,N,N-trimethyl-, dioctadecyl phosphate (9CI) (CA INDEX NAME)

CM 1

CRN 106347-16-4

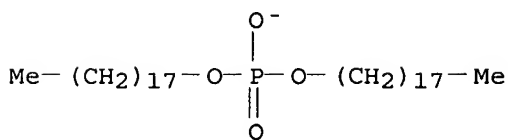
CMF C39 H62 N O2



CM 2

CRN 84841-00-9

CMF C36 H74 O4 P



=> save

ENTER L#, L# RANGE, ALL, OR (END):yc10539807/a

YC10539807/A IS NOT A VALID L#, L# RANGE, OR ALL

Enter a valid L-number or L-number range for the items to be saved or

ALL to SAVE all session queries as an L-number list. To see all

L-numbers defined in this session, enter END. Then enter DISPLAY

HISTORY at an arrow prompt (=>).

ENTER L#, L# RANGE, ALL, OR (END):14

ENTER NAME OR (END):yc10539807/a

ANSWER SET L4 HAS BEEN SAVED AS 'YC10539807/A'

HISTORY at an arrow prompt (=>).
ENTER L#, L# RANGE, ALL, OR (END):14
ENTER NAME OR (END):yc10539807/a
ANSWER SET L4 HAS BEEN SAVED AS 'YC10539807/A'

=> s l4 and phase-transfer agent
1690902 PHASE
353345 PHASES
1839674 PHASE
(PHASE OR PHASES)
781065 TRANSFER
25566 TRANSFERS
793479 TRANSFER
(TRANSFER OR TRANSFERS)
793909 AGENT
1154928 AGENTS
1624410 AGENT
(AGENT OR AGENTS)
659 PHASE-TRANSFER AGENT
(PHASE(W) TRANSFER(W) AGENT)
L13 0 L4 AND PHASE-TRANSFER AGENT

=> s l4 and phase transfer
1690902 PHASE
353345 PHASES
1839674 PHASE
(PHASE OR PHASES)
781065 TRANSFER
25566 TRANSFERS
793479 TRANSFER
(TRANSFER OR TRANSFERS)
14182 PHASE TRANSFER
(PHASE(W) TRANSFER)
L14 1 L4 AND PHASE TRANSFER

=> d ibib abs hitstr tot

L14 ANSWER 1 OF 1 CAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2003:271685 CAPLUS Full-text
DOCUMENT NUMBER: 138:287414
TITLE: Preparation of hydroquinone alkyl ethers
INVENTOR(S): Kubo, Hideo; Yamaguchi, Katsuji; Shirai, Akihiro
PATENT ASSIGNEE(S): Nippon Soda Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 2003104926	A2	20030409	JP 2001-299629	20010928
PRIORITY APPLN. INFO.:			JP 2001-299629	20010928
OTHER SOURCE(S):	CASREACT 138:287414			

AB Title compds., useful as sensitizers for photopolymn., etc. (no data), are
prepd. by alkylation of hydroquinones by C.gtoeq.3 alkylating agents in the
presence of bases and quaternary ammonium salts having C.gtoeq.5 substituents
on N. Anthraquinone was alkylated by BuI in THF/H2O in the presence of

trioctylmethylammonium chloride, Na₂S₂O₄, and NaOH at 40-50.degree. for 5 h to give 85% 9,10-dibutoxyanthracene.

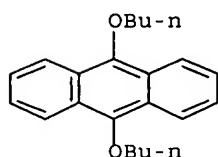
IT 76275-14-4P

RL: IMF (Industrial manufacture); SPN (Synthetic preparation); PREP (Preparation)

(prepn. of hydroquinone alkyl ethers from hydroquinones using quaternary ammonium salts)

RN 76275-14-4 CAPLUS

CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)



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---Logging off of STN---

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Executing the logoff script...

=> LOG Y

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

139.15

306.74

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)

SINCE FILE

TOTAL

ENTRY

SESSION

CA SUBSCRIBER PRICE

-13.50

-13.50

STN INTERNATIONAL LOGOFF AT 08:43:10 ON 14 AUG 2006